

Supplementary Information

Design principle for p-type oxide gate layer on AlGaN/GaN toward normally-off HEMTs: Li-doped NiO as model †

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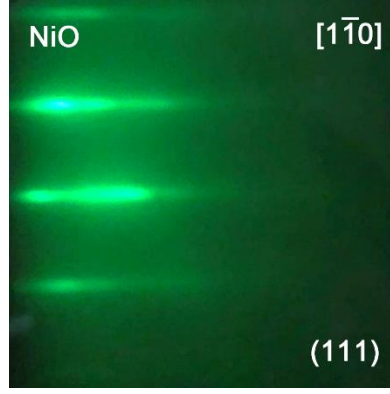


Fig. S1. RHEED pattern of NiO thin films on Al_2O_3 substrates.

Fig. S1 shows the RHEED pattern of NiO thin films on Al_2O_3 substrates. The above similar RHEED pattern with NiO on GaN indicates the similar epitaxial crystal structure of NiO thin films on GaN and Al_2O_3 substrates.

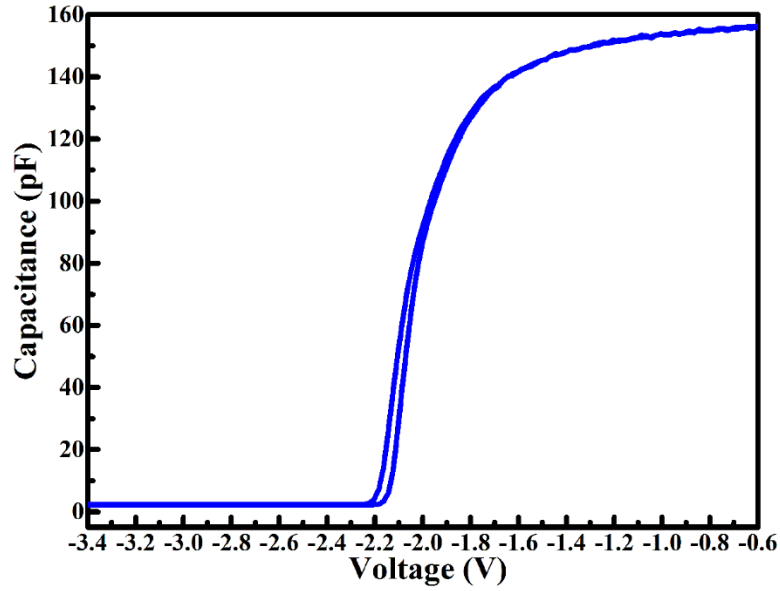


Fig. S2. C-V characteristic of $\text{Pt}/\text{Ni}_{0.75}\text{Li}_{0.25}\text{O}/\text{AlGaIn}/\text{GaN}/\text{Si}$ heterostructure.

Fig. S2 displays C-V curve of $\text{Pt}/\text{Ni}_{0.75}\text{Li}_{0.25}\text{O}/\text{AlGaIn}/\text{GaN}/\text{Si}$ heterostructure. The small voltage window indicates good interfacial state at $\text{Ni}_{0.75}\text{Li}_{0.25}\text{O}/\text{AlGaIn}$ interface.

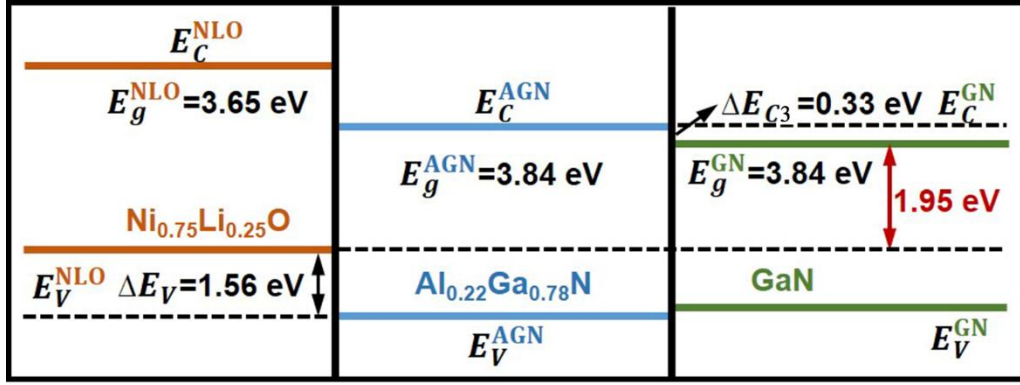


Fig. S3. Band alignment of $Ni_{0.75}Li_{0.25}O/Al_{0.22}Ga_{0.78}N/GaN$ heterostructure.

Fig. S3 shows the band alignment of $Ni_{0.75}Li_{0.25}O/Al_{0.22}Ga_{0.78}N/GaN$ heterostructure. The ratios of conduction band discontinuities to valence band discontinuities are 75:25 for AlGaN/GaN interface in the reported results.³⁶ Thus the valance band offset (ΔE_{c3}) value at $Al_{0.22}Ga_{0.78}N/GaN$ interface is calculated to be 0.33 eV. Therefore, intrinsic $E_c^{GaN} - E_v^p$ value is determined to be 1.95 eV calculated by $E_g^{AGN} - \Delta E_v - \Delta E_{c3}$.